

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for manufacturing a ceramic material coating method of forming a coating film on a base by applying a ceramic material including a complex oxide to the base by spin coating, the method comprising:

applying a ceramic material to a substrate;

a first rotational step of rotating the substratebase at a first predetermined rotational speed for a first time;

a second rotational step of rotating the substratebase at a second rotational speed lower than the first rotational speed in the first rotational step for a second time; and

a third rotational step of rotating the substratebase at a rotational third speed higher than the second rotational speed in the second rotational step. for a third time; and

forming the ceramic film including a perovskite structure by a heat treatment.

2. (Currently Amended) The ceramic material coating method as defined in claim 1, wherein the third rotational speed in the third rotational step is being higher than the first rotational speed in the first rotational step.

3. (Currently Amended) The ceramic material coating method as defined in claim 1, further comprising:

a step of drying the ceramic material coated on the substrate coating film after rotating the substrate at the third speed forming the coating film by the spin coating.

4. (Currently Amended) The ceramic material coating method as defined in claim 3, wherein the step of drying the ceramic material being coating film is performed by blowing gas onto the ceramic material the coating film.

5. (Currently Amended) The ceramic material coating method as defined in claim 1,

wherein the ceramic material includes including at least one of a sol-gel raw material and an MOD raw material, the ~~sol-gel~~ ~~sol-gel~~ raw material including at least one of a hydrolysate and a polycondensate of the complex oxide, the MOD raw material including constituent elements of the complex oxide in an organic solvent.

6. (Currently Amended) The ~~ceramic material coating~~ method as defined in claim 1, the substrate including an electrode layer including platinum, ruthenium, rhodium, palladium, osmium or iridium,

wherein the base to which the ceramic material is being applied on the electrode in the applying the ceramic material includes an electrode layer made of a platinum group element on a surface of the base.

7. (Withdrawn) A ceramic film obtained by the ceramic material coating method as defined by claim 1.

8. (Withdrawn) A ceramic film obtained by the ceramic material coating method as defined by claim 2.

9. (Withdrawn) A ceramic film obtained by the ceramic material coating method as defined by claim 3.

10. (Withdrawn) A ceramic film obtained by the ceramic material coating method as defined by claim 4.

11. (New) The method as defined in claim 1, the first time being shorter than the third time.

12. (New) The method as defined in claim 1, the ceramic material including at least one of Bi, Ti, La and Pb.

13. (New) The method as defined in claim 1, the ceramic material including at least one of Si and Ge.

14. (New) The method as defined in claim 8, the ceramic material further including at least one of Si and Ge.

15. (New) The method as defined in claim 1, the ceramic film including Pb, Zr, and Ti.

16. (New) The method as defined in claim 1, the ceramic film including PZT, BiLaTiO, BiTiO or SrBiTaO.

17. (New) A method for manufacturing a ferroelectric memory comprising the method as defined as claim 1.

18. (New) A method for manufacturing a semiconductor device comprising the method as defined as claim 1.